ABSTRACT

[Problem] A footprint is reduced while securing a maintenance area.

[Solving Means] A substrate processing apparatus includes: a first processing module including a first processing container configured to process a substrate; a second processing module including a second processing container disposed adjacent to the first processing container and configured to process the substrate; a first exhaust box disposed adjacent to a back surface of the first processing module and accommodating a first exhaust system configured to evacuate an inside of the first processing container; a first supply box disposed adjacent to a side of the first exhaust box opposite to a side adjacent to the back surface of the first processing module and accommodating a first supply system configured to supply a processing gas into the first processing container; a second exhaust box disposed adjacent to a back surface of the second processing module and accommodating a second exhaust system configured to evacuate an inside of the second processing container; and a second supply box disposed adjacent to a side of the second exhaust box opposite to a side adjacent to the back surface of the second processing module and accommodating a second supply system configured to supply a processing gas into the second processing container, wherein the first exhaust box is disposed at an outer corner positioned on a side opposite to the second processing module on the back surface of the first processing module, and the second exhaust box is disposed at an outer corner positioned on a side opposite to the first processing module on the back surface of the first processing module.

FIGURE 1